Search History

(HEATLUS, INSPEC, JAPEO, WOPAFAU)

=> d 18 1-4 abs,bib

ANSWER 1 OF 4 USPATFULL on STN L8 AB With respect to a liquid phase growth method for a silicon crystal in which the silicon crystal is grown on a substrate by immersing the substrate in a solvent or allowing the substrate to contact the solvent, a gas containing a raw material and/or a dopant is supplied to the solvent after at least a part of the gas is decomposed by application of energy thereto. In this manner, a liquid phase growth method for a silicon crystal, the method capable of achieving continuous growth and suitable for mass production, a manufacturing method for a solar cell and a liquid phase growth apparatus for a silicon crystal are provided. CAS INDEXING IS AVAILABLE FOR THIS 2004:86293 USPATRULL Liquid phase growth method for silicon crystal manufacturing method and liquid phase growth apparatus for TI silicon crystal Nishida, Shoji, Nara, JAPAN IN Yoshino Takehito, Nara, JAPAN Iwane, Masaki, Nara JAPAN Mizutani, Masaki, Nara JAPAN CANON KABUSHIKI KAISHA Tokyo, JAPAN (non-U.S. corporation) PΑ ΡI US 2004065251 US 2003-676094 20031002 (10) AI PRAI JP 2002-294897 20021008 DT Utility FS APPLICATION FITZPATRICK CELLA HARPER & SCINTO, 30 ROCKEFELLER PLAZA, NEW YORK, NY, LREP 10112 CLMN Number of Claims: 33 ECL Exemplary Claim: 1 DRWN 5 Drawing Page(s) LN.CNT 964 CAS INDEXING IS AVAILABLE FOR THIS PATENT. L8 ANSWER 2 OF 4 USPATFULL on STN AR Provided are a liquid phase growth method of silicon crystal comprising a step of injecting a source gas containing at least silicon atoms into a solvent to decompose the source gas and, simultaneously therewith, dissolving the silicon atoms into the solvent, thereby supplying the silicon atoms into the solvent, and a step of dipping or contacting a substrate into or with the solvent, thereby growing a silicon crystal on the substrate; and a method of producing a solar cell utilizing the aforementioned method. Also provided is a liquid phase growth apparatus of a silicon crystal comprising means for holding a solvent in which silicon atoms are dissolved, and means for dipping or contacting a substrate into or with the solvent, the apparatus further comprising means for injecting a source gas containing at least silicon atoms into the solvent. These provide a liquid phase growth method of a silicon crystal and a production method of a solar cell each having high volume productivity and permitting continuous growth.

```
AN
         2002:211323 USPATFULL
 ΤI
        Liquid phase growth method of
         silicon crystal, method of producing solar, cell, and
         liquid phase growth apparatus
 IN
        Nishida, Shoji, Kanagawa-ken, JAPAN
         Nakagawa, Katsumi, Kanagawa-ken, JAPAN
         Ukiyo, Noritaka, Kanagawa-ken, JAPAN
         Iwane, Masaaki Kanagawa-ken, JAPAN
        US 2002112660
                           A1
                                 20020822
       US 2002-120357
                           A1
                                 20020412 (10)
         Division of Ser. No. US 1998-208377, filed on 10 Dec 1998, GRANTED, Pat.
        No. US 6391108
 PRAI
        JP 1997-342709
                             19971212
 DT
        Utility
 FS
        APPLICATION
 LREP
        FITZPATRICK CELLA HARPER & SCINTO, 30 ROCKEFELLER PLAZA, NEW YORK, NY,
 CLMN
        Number of Claims: 31
 ECL
        Exemplary Claim: 1
 DRWN
         4 Drawing Page(s)
 LN.CNT 614
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.
 L8,
       ANSWER 3 OF 4 USPATFULL on STN
 AB
         Provided are a liquid phase growth method
        of silicon crystal comprising a step of injecting a
         source gas containing at least silicon atoms into a solvent to decompose
         the source gas and, simultaneously therewith, dissolving the silicon
        atoms into the solvent, thereby supplying the silicon atoms into the
         solvent, and a step of dipping or contacting a substrate into
        or with the solvent, thereby growing a silicon
         crystal on the substrate; and a method of producing a solar cell
        utilizing the aforementioned method. Also provided is a liquid
        phase growth apparatus of a silicon
        crystal comprising means for holding a solvent in which
         silicon atoms are dissolved, and means for dipping or contacting
         a substrate into or with the solvent, the apparatus
         further comprising means for injecting a source gas containing at least
        silicon atoms into the solvent. These provide a liquid
        phase growth method of a silicon
         crystal and a production method of a solar cell each having high
        volume productivity and permitting continuous growth.
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.
 AN
         2002:10790 USPATFULL
 ΤI
         LIQUID PHASE GROWTH METHOD OF
         SILICON CRYSTAL, METHOD OF PRODUCING SOLAR CELL, AND
         LIQUID PHASE GROWTH APPARATUS
 TN
        NISHIDA, SHOJI, HIRATSUKA-SHI, JAPAN
        NAKAGAWA, KATSUMI, ATSUGI-SHI, JAPAN
        UKIYO, NORITAKA, ATSUGI-SHI, JAPAN
         IWANE, MASAAKI, ATSUGI-SHI, JAPAN
 ΡI
        US 2002005158
                            Α1
                                 20020117
        US 6391108
                            B2
                                 20020521
1 AI
        US 1998-208377
                            A1
                                 19981210 (9)
 PRAI
        JP 1997-342709
                             19971212
 DT
        Utility
 FS
        APPLICATION
 LREP
        FITZPATRICK CELLA HARPER & SCINTO, 30 ROCKEFELLER PLAZA, NEW YORK, NY,
 CLMN
        Number of Claims: 31
 ECL
        Exemplary Claim: 1
 DRWN
        4 Drawing Page(s)
```

```
LN.CNT 614
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
```

```
L8
     ANSWER 4 OF 4 USPAT2 on STN
AΒ
       Provided are a liquid phase growth method
       of silicon crystal comprising a step of injecting a
       source gas containing at least silicon atoms into a solvent to decompose
       the source gas and, simultaneously therewith, dissolving the silicon
       atoms into the solvent, thereby supplying the silicon atoms into the
       solvent, and a step of dipping or contacting a substrate into
       or with the solvent, thereby growing a silicon
       crystal on the substrate; and a method of producing a solar cell
       utilizing the aforementioned method. Also provided is a liquid
       phase growth apparatus of a silicon
       crystal comprising means for holding a solvent in which
       silicon atoms are dissolved, and means for dipping or contacting
       a substrate into or with the solvent, the apparatus
       further comprising means for injecting a source gas containing at least
       silicon atoms into the solvent. These provide a liquid
       phase growth method of a silicon
       crystal and a production method of a solar cell each having high
       volume productivity and permitting continuous growth.
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
AN
       2002:10790 USPAT2
       Liquid phase growth method of
TI
       silicon crystal, method of producing solar cell, and
       liquid phase growth apparatus
IN
       Nishida, Shoji, Hiratsuka, JAPAN
       Nakagawa, Katsumi, Atsugi, JAPAN
       Ukiyo, Noritaka, Atsugi, JAPAN
       Iwane, Masaaki, Atsugi, JAPAN
PA
       Canon_Kabushiki Kaisha, Tokyo, JAPAN (non-U.S. corporation)
PΙ
       US 6391108
                          B2
                                20020521
       US 1998-208377
ΑI
                                19981210 (9)
       JP 1997-342709
                           19971212
PRAI
DT
       Utility
FS
       GRANTED
EXNAM Primary Examiner: Utech, Benjamin L.; Assistant Examiner: Anderson,
       Matthew
LREP
       Fitzpatrick, Cella, Harper & Scinto
CLMN
       Number of Claims: 18
ECL
       Exemplary Claim: 1
DRWN
       4 Drawing Figure(s); 4 Drawing Page(s)
LN.CNT 552
CAS INDEXING IS AVAILABLE FOR THIS PATENT.
=> d his
      (FILE 'HOME' ENTERED AT 13:31:15 ON 29 MAR 2005)
     FILE 'HCAPLUS, INSPEC, JAPIO, INPADOC, USPATFULL, USPAT2' ENTERED AT
     13:31:58 ON 29 MAR 2005
          27937 S (LPE OR LIQUID(W) PHASE(W) EPITAX? OR LIQUID(W) PHASE(W) GROW?)
L1
L2
         193444 S (SI OR SILICON) (8A) (CRYSTAL?)
L3
         114745 S (SUBSTRATE#) (6A) (SOLVENT# OR LIQUID#)
L4
         178185 S (DOPANT#)
L5
          21222 S (DECOMPOSIT? (4A) GAS?)
L6
         338325 S (RAW(W)MATERIAL#)
L7
        4630569 S (METAL#)
              4 S L1 AND L2 AND L3 AND L4 AND L5 AND L6 AND L7
L8
```

George K. Ny (71) 540 - 8700 117/94 - 100 Tenton 100

10/676,094 Finchize Restroction

Examiner & Notes

* Priority document JP-2002-294897 filed on 19/8/2002

s (LPE or liquid (w) phase (w) epitosog)
\$ (Si or silicon) (Ba) (crystal?)
\$ (Substrate #) (ba) (solventation liquid#)
\$ (depart)
\$ (decimposit? (La) gas?)
\$ (law(w) maternia/#)
\$ (metal #)

Claim I line and or "
Claim I line 3, 4, 6, 8 "and or "
Claim I line 3 " and lor "
Claim It, line 3; "and for "
Claim 14, line 3; "and for "
Claim 15, line 3; "and for "
Claim 13 lines 3, 4, 4, 4 and for "
Claim 15, lines 3, 4, 4, 4 and for "

Over claims /-23 of 10/676, 094

ODP Roj: Craims 1-20 of 215. Appl 10/100,357 over claims 1-23 of U.S. Appl 10/676, 094,

